## **REFERENCE LIST**

**SEMICONDUCTOR** 

SOLAR

PHARMA

POWER GENERATION

**FOOD & BEVERAGE** 

PULP AND PAPER

CHEMICAL

OIL AND GAS

MINING

**AEROSPACE AND TRANSPORT** 

STANDARD EQUIPMENT



## Functional Water Systems



The following list gives some information about just a selection of the many hundreds of Functional Water units that have been supplied to a very wide variety of clients throughout the electronics industry, worldwide.

Unfortunately, due to the secrecy agreements in place with most of our clients, we are unable to disclose our client's names, their factory locations, or much information about the applications they are used for. We take the confidences of all our clients very seriously and hope that you will understand this. However, we hope that the list below will demonstrate clearly that we have a great deal of experience in the production of both oxidising and reducing ultrapure water for use in a variety of applications within the electronics industry.

If you would like to receive further selected information about any of the following applications, or further information about the use and applications of Functional Water units, please do contact us at the above address and we will be pleased to provide additional information.





Model G-2400

Model H-300

In the following list, the various types of Functional Water units supplied are as listed below:

Type I: Electrolytic Ionised water, Type II: Gas Dissolved Water (H<sub>2</sub> + O<sub>3</sub>)

H: Hydrogen Water, O: Ozone water, OR: Water degasser unit, NH: Ammonia

400	Туре	Flow Rate (I/h)	Objective	Note
1	I	400	LSI manufacture	CMP/Wafer cleaning
1	ı	400	LCD manufacture	TFT process
1	ı	100	LCD manufacture	TFT process
100   Equipment manufacturer   Wet scrubber     100   Wafer manufacture   Post polish cleaning /Wafer cleaning     1080   LCD manufacture   LCD process     1200   LSI manufacture   LCD process     1200   Equipment manufacturer   Wet scrubber/Wafer cleaning     1600     1   00	ı	100	Wafer manufacture	Post polish cleaning /Wafer cleaning
100 Wafer manufacture Post polish cleaning /Wafer cleaning   1080 LCD manufacture LCD process   1100 / 2400 / 3600 LCD manufacture LCD process   11200 LSI manufacture CMP   1200 Equipment manufacturer Wet scrubber/Wafer cleaning   1600   1100   1200 LCD manufacture TFT process   12400 LCD manufacture Cell process cleaning   1100   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture (RTD)   1200 Wafer manufacture (RTD)   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture (RTD)   1200 Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1110   1200 Wafer manufacture Post polish cleaning /Wafer cleaning   1200 Wafer manufacture Post polish cleaning /Wafer cleaning /Wafer Cleaning /Wafer Cleaning /Wafer /Wafer /Wafer /Wafer /Wafer /Wafer /Wafer /Wafer /Wafer /Waf	ı	100	LSI manufacture	RCA cleaning
1080	ı	100	Equipment manufacturer	wet scrubber
1	ı	100	Wafer manufacture	Post polish cleaning /Wafer cleaning
I 1200 LSI manufacture CMP  I 1200 Equipment manufacturer Wet scrubber/Wafer cleaning  I 600  II O <sub>3</sub> 180 / H <sub>2</sub> 300 LCD manufacture TFT process  I 2400 LCD manufacture TFT process  H 48000 LCD manufacture TFT process  H 2400 LCD manufacture Cell process cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 2400 Wafer manufacture Post polish cleaning /Wafer cleaning  I 200 Equipment manufacture CMP  I 200 Wafer manufacture (RTD) Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 1000 / H <sub>2</sub> 1200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400  H 300 Equipment manufacture TFT process  I LCD manufacture TFT process  I LCD manufacture TFT process  I 60 R&D Analysis equipment cleaning  TFT process	ı	1080	LCD manufacture	LCD process
1	II	1200 / 2400 /3600	LCD manufacture	LCD process
G00	ı	1200	LSI manufacture	CMP
II	ı	1200	Equipment manufacturer	Wet scrubber/Wafer cleaning
I 2400 LCD manufacture TFT process  H 48000 LCD manufacture TFT process  H 2400 LCD manufacture Cell process cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 2400 Wafer manufacture Post polish cleaning /Wafer cleaning  I 200 Equipment manufacturer CMP  I 200 Wafer manufacture (RTD) Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 1200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400  H 300 Equipment manufacture Post polish cleaning /Wafer cleaning  H CD manufacture TFT process  I CD manufacture TFT process  I 60 R&D Analysis equipment cleaning	ı	600		
H       48000       LCD manufacture       TFT process         H       2400       LCD manufacture       Cell process cleaning         II       O <sub>3</sub> 600 / H <sub>2</sub> 1200       Wafer manufacture       Post polish cleaning /Wafer cleaning         II       O <sub>3</sub> 600 / H <sub>2</sub> 2400       Wafer manufacture       CMP         I       200       Equipment manufacture (RTD)       Post polish cleaning /Wafer cleaning         II       O <sub>3</sub> 1200 / H <sub>2</sub> 4200       Wafer manufacture       Post polish cleaning /Wafer cleaning         H       2400       LSI manufacture       Wafer cleaning         II       O <sub>3</sub> 600 / H <sub>2</sub> 1200         II       O <sub>3</sub> 300 / H <sub>2</sub> 4200       Wafer manufacture       Post polish cleaning /Wafer cleaning         H       2400         H       300       Equipment manufacture       TFT process         I       LCD manufacture       TFT process         I       LCD manufacture       TFT process         I       60       R&D       Analysis equipment cleaning         H       LCD manufacture       TFT process	II	O <sub>3</sub> 180 / H <sub>2</sub> 300	LCD manufacture	TFT process
H 2400 LCD manufacture Cell process cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 2400 Wafer manufacture Post polish cleaning /Wafer cleaning  I 200 Equipment manufacturer CMP  I 200 Wafer manufacture (RTD) Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400  H 300 Equipment manufacture  H 1 CD manufacture TFT process  I 1 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	ı	2400	LCD manufacture	TFT process
II O <sub>3</sub> 600 / H <sub>2</sub> 1200 Wafer manufacture Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 2400 Wafer manufacture Post polish cleaning /Wafer cleaning  I 200 Equipment manufacturer CMP  I 200 Wafer manufacture (RTD) Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400 LSI manufacture Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400  H 300 Equipment manufacture  H LCD manufacture TFT process  I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	Н	48000	LCD manufacture	TFT process
II O <sub>3</sub> 600 / H <sub>2</sub> 2400 Wafer manufacture Post polish cleaning /Wafer cleaning I 200 Equipment manufacturer CMP I 200 Wafer manufacture (RTD) Post polish cleaning /Wafer cleaning II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning II O <sub>3</sub> 600 / H <sub>2</sub> 1200 II O <sub>3</sub> 600 / H <sub>2</sub> 1200 III O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning II CHO manufacture TFT process I CCD manufacture TFT process I 60 R&D Analysis equipment cleaning II CCD manufacture TFT process I CCD manufacture TFT process I TFT process	Н	2400	LCD manufacture	Cell process cleaning
I 200 Equipment manufacturer CMP  I 200 Wafer manufacture (RTD) Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400 LSI manufacture Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400  H 300 Equipment manufacturer  H LCD manufacture TFT process  I CD manufacture TFT process  I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	II	O <sub>3</sub> 600 / H <sub>2</sub> 1200	Wafer manufacture	Post polish cleaning /Wafer cleaning
I 200 Wafer manufacture (RTD) Post polish cleaning /Wafer cleaning  II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400 LSI manufacture Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400  H 300 Equipment manufacturer  H LCD manufacture TFT process  I CD manufacture TFT process  I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	II	O <sub>3</sub> 600 / H <sub>2</sub> 2400	Wafer manufacture	Post polish cleaning /Wafer cleaning
II O <sub>3</sub> 1200 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400 LSI manufacture Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400  H 300 Equipment manufacturer  H LCD manufacture TFT process  I G0 R&D Analysis equipment cleaning  H LCD manufacture TFT process	ı	200	Equipment manufacturer	CMP
H 2400 LSI manufacture Wafer cleaning  II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning / Wafer cleaning  H 2400  H 300 Equipment manufacturer  H LCD manufacture TFT process  I LCD manufacture TFT process  I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	ı	200	Wafer manufacture (RTD)	Post polish cleaning /Wafer cleaning
II O <sub>3</sub> 600 / H <sub>2</sub> 1200  II O <sub>3</sub> 300 / H <sub>2</sub> 4200 Wafer manufacture Post polish cleaning /Wafer cleaning  H 2400  H 300 Equipment manufacturer  H LCD manufacture TFT process  I LCD manufacture TFT process  I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	II	O <sub>3</sub> 1200 / H <sub>2</sub> 4200	Wafer manufacture	Post polish cleaning /Wafer cleaning
II       O3 300 / H2 4200       Wafer manufacture       Post polish cleaning /Wafer cleaning         H       2400         H       300       Equipment manufacturer         H       LCD manufacture       TFT process         I       LCD manufacture       TFT process         I       60       R&D       Analysis equipment cleaning         H       LCD manufacture       TFT process	Н	2400	LSI manufacture	Wafer cleaning
H 2400  H 300 Equipment manufacturer  H LCD manufacture TFT process  I LCD manufacture TFT process  I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	II	O <sub>3</sub> 600 / H <sub>2</sub> 1200		
H 300 Equipment manufacturer  H LCD manufacture TFT process  I LCD manufacture TFT process  I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	II	O <sub>3</sub> 300 / H <sub>2</sub> 4200	Wafer manufacture	Post polish cleaning /Wafer cleaning
H LCD manufacture TFT process  I LCD manufacture TFT process  I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	Н	2400		
I LCD manufacture TFT process  I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	Н	300	Equipment manufacturer	
I 60 R&D Analysis equipment cleaning  H LCD manufacture TFT process	Н		LCD manufacture	TFT process
H LCD manufacture TFT process	I		LCD manufacture	TFT process
	I	60	R&D	Analysis equipment cleaning
II LSI manufacture Post polish cleaning /Wafer cleaning	Н		LCD manufacture	TFT process
	11		LSI manufacture	Post polish cleaning /Wafer cleaning

Туре	Flow Rate (I/h)	Objective	Note
II	O <sub>3</sub> 1200 / H <sub>2</sub> 1200	Lens manufacture	Post polish cleaning
Н	900	LSI manufacture	Final cleaning
Н	900	LSI manufacture	Final cleaning
Н	900	LSI manufacture	CMP
Н	900	Mask manufacture	Mask cleaning
Н	2400	HD manufacture	HD cleaning
Н	2400	Mask manufacture	Mask cleaning
Н	900	Mask manufacture	Mask cleaning
ı	600	Equipment manufacturer	Mask cleaning
Н	900	LSI manufacture	CMP
0	1200	Wafer manufacture	Final cleaning
0	1200	Wafer manufacture	Final cleaning
0	1200	Wafer manufacture	Final cleaning
0	1200	Wafer manufacture	Final cleaning
0	1200	Wafer manufacture	Final cleaning
0	1200	Wafer manufacture	Final cleaning
0	1200	Wafer manufacture	Final cleaning
Н	900	R&D	R&D
Н	2400	Mask manufacture	Mask cleaning
Н	900	LSI manufacture	CMP
Н	900	Equipment manufacturer	CMP
Н	1200	Mask manufacture	Mask cleaning
Н	1200	Mask manufacture	Mask cleaning
Н	900	Equipment manufacturer	R&D
I	600	Equipment manufacturer	R&D
Н	900	Equipment manufacturer	Cleaning machine
Н	1200	Mask manufacture	Mask cleaning
0	1200	Wafer manufacture	Final cleaning
0	1200	Wafer manufacture	Final cleaning
Н	2400	R&D	R&D
Н	2400	R&D	R&D

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Туре	Flow Rate (I/h)	Objective	Note
II	O <sub>3</sub> 600 / H <sub>2</sub> 600	Wafer manufacture	Final cleaning
II	O <sub>3</sub> 600 / H <sub>2</sub> 1200	Lens manufacture	Post polish cleaning
ı	200	Equipment manufacturer	Cleaning machine
Н	2400	Wafer manufacture	Mask cleaning
Н	7200	LCD manufacture	Glass cleaning
Н	900	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Cleaning machine
Н	1200	Equipment manufacturer	Cleaning machine
Н	2400	Equipment manufacturer	Cleaning machine
Н	2400	LSI manufacture	CMP
Н	2400	R&D	R&D
II	O <sub>3</sub> 600 / H <sub>2</sub> 1200		
Н	900	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
II	O <sub>3</sub> 1200 / H <sub>2</sub> 1200		Glass cleaning
OR	2400	Equipment manufacturer	Cleaning machine
Н	900	Equipment manufacturer	Mask cleaning
Н	900	Equipment manufacturer	Mask cleaning
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP

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Туре	Flow Rate (I/h)	Objective	Note
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
II	O <sub>3</sub> 1200 / H <sub>2</sub> 1200		
OR	1500		R&D
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
Н	1200	LSI manufacture	CMP
Н	3600	Glass manufacture	
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
Н	300		R&D
Н	900	LSI manufacture	BEOL
Н	1200	LSI manufacture	CMP
Н	900	Equipment manufacturer	Cleaning machine
Н	300	Equipment manufacturer	Cleaning machine
Н	120	Equipment manufacturer	Cleaning machine
Н	2400	LSI manufacture	CMP
Н	2400	LSI manufacture	CMP
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine

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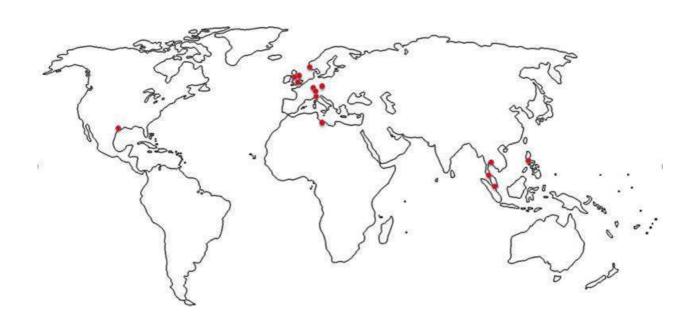
Туре	Flow Rate (I/h)	Objective	Note
OR	2400	Equipment manufacturer	Cleaning machine
Н	300	Equipment manufacturer	Cleaning machine
Н	300		
Н	900	LCD manufacture	Glass cleaning
OR	2400	Equipment manufacturer	Cleaning machine
0	1200	Mask manufacture	Mask cleaning
Н	300	Equipment manufacturer	Cleaning machine
0	120	Equipment manufacturer	Cleaning machine
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
Н	900	LSI manufacture	CMP
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	270	LSI manufacture	
OR		Equipment manufacturer	Cleaning machine
Н	300	Equipment manufacturer	Cleaning machine
Н	2400	LSI manufacture	CMP
Н	300		
OR		Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine

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Туре	Flow Rate (I/h)	Objective	Note
0	2000	LCD manufacture	
Н	1200	LCD manufacture	
0	120	Equipment manufacturer	Cleaning machine
Н	300	Equipment manufacturer	Cleaning machine
0	2400	LCD manufacture	
Н	2400	LCD manufacture	
NH	2400	Component cleaning	Tool supplier for new process
NH	2400	Component cleaning	Tool supplier for new process
NH	2400	Component cleaning	Tool supplier for new process
NH	2400	Component cleaning	Tool supplier for new process
NH	2400	Component cleaning	Tool supplier for new process

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H+E ranks among the world's leading suppliers in the fields of: water & wastewater treatment, and energy efficiency. Based on its global presence, the H+E GROUP has completed projects in over 50 countries.





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